Title (en)

SCATTEROMETRY ALIGNMENT FOR IMPRINT LITHOGRAPHY

Title (de)

STREUUNGSMESSAUSRICHTUNG FÜR DIE DRUCKLITHOGRAPHIE

Title (fr)

ALIGNEMENT PAR DIFFUSIOMETRIE POUR LITHOGRAPHIE PAR EMPREINTE

Publication

EP 1573395 A2 20050914 (EN)

Application

EP 03767009 A 20030731

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- US 21089402 A 20020801

Abstract (en)

[origin: WO2004013693A2] Described are methods for patterning a substrate by imprint lithography. Imprint lithography is a process in which a liquid is dispensed onto a substrate. A template is brought into contact with the liquid and the liquid is cured. The cured liquid includes an imprint of any patterns formed in the template. Alignment of the template with a previously formed layer on a substrate, in one embodiment, is accomplished by using scatterometry.

IPC 1-7

G03F 1/00

IPC 8 full level

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